L	Hits	Search Text	DB	Time stamp
Number	1	10/665412	USPAT;	2004/07/30
	•	10/003412	US-PGPUB;	13:24
			EPO; JPO;	13.24
			DERWENT;	
			IBM_TDB	
	46291	(resist or photoresist or photopolymer) with	USPAT;	2004/07/30
-	7020.	(Sil or silicon)	US-PGPUB;	13:25
		(on or smoon)	EPO; JPO;	13.23
			DERWENT;	
			IBM_TDB	
	93664	(resist or photoresist or \$6lithogr\$6) and	USPAT;	2004/07/30
	33334	(re\$work or rework or strip or stripped ir	US-PGPUB;	13:44
		stripping)	EPO; JPO;	13.44
		Supplied,	DERWENT;	
			IBM_TDB	
_	10244	((resist or photoresist or photopolymer)	USPAT;	2004/07/30
		with (Si! or silicon)) and ((resist or	US-PGPUB;	13:28
		photoresist or \$6lithogr\$6) and (re\$work or	EPO; JPO;	13.20
		rework or strip or stripped ir stripping))	DERWENT;	
		Terrorit of Stripping)	IBM_TDB	
	1133	(((resist or photoresist or photopolymer)	USPAT;	2004/07/30
	1100	with (Si! or silicon)) and ((resist or	US-PGPUB;	15:57
		photoresist or \$6lithogr\$6) and (re\$work or	EPO; JPO;	13.37
		rework or strip or stripped ir stripping))) and	DERWENT;	
		(solvent same (THF or PGMEA or DMSO or	IBM_TDB	
		ketones or esters or lactates))	15155	
	85	((((resist or photoresist or photopolymer)	USPAT;	2004/07/30
		with (Si! or silicon)) and ((resist or	US-PGPUB;	13:31
		photoresist or \$6lithogr\$6) and (re\$work or	EPO; JPO;	10.01
		rework or strip or stripped ir stripping))) and	DERWENT;	
		(solvent same (THF or PGMEA or DMSO or	IBM_TDB	
		ketones or esters or lactates))) and		
		((re\$coat or coat) same (re\$expos\$4 or		
		expos\$4))		
.	80443	(resist or photoresist or \$6lithogr\$6) and (USPAT;	2004/07/30
		strip or stripped or stripping)	US-PGPUB;	15:19
		71 0,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	619	((resist or photoresist or \$6lithogr\$6) and (USPAT;	2004/07/30
		strip or stripped or stripping)) and (re\$work	US-PGPUB;	13:46
		or rework)	EPO; JPO;	
		,	DERWENT;	
			IBM_TDB	
•	39	(((resist or photoresist or \$6lithogr\$6) and (USPAT;	2004/07/30
		strip or stripped or stripping)) and (re\$work	US-PGPUB;	16:40
		or rework)) and ((solvent or solution) same	EPO; JPO;	
		(THF or PGMEA or DMSO or ketones or	DERWENT;	
1		esters or lactates))	IBM_TDB	

			1	
-	1400	430/329	USPAT;	2004/07/30
			US-PGPUB;	15:10
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1	430/329 and (chemical\$3 near amplif\$9)	USPAT;	2004/07/30
		with (si or sily\$9 or silane or	US-PGPUB;	15:15
	Ī	\$9sesquioxane)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	1	430/329 and ((chemical\$3 near amplif\$9)	USPAT;	2004/07/30
		with (si or silo\$9 or silane or	US-PGPUB;	15:16
		\$9sesquioxane))	EPO; JPO;	
ĺ			DERWENT;	
	1		IBM_TDB	
-	8	430/329 and ((chemical\$3 near amplif\$9)	USPAT;	2004/07/30
		with (Si or silicon or (silicon near (bearining	US-PGPUB;	15:53
1		or containing))))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	553	430/329 and (resist or photoresist or	USPAT;	2004/07/30
		\$6lithogr\$6) and (strip or stripped or	US-PGPUB;	15:47
		stripping)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	27	(430/329 and (resist or photoresist or	USPAT;	2004/07/30
		\$6lithogr\$6) and (strip or stripped or	US-PGPUB;	15:49
		stripping)) and (chemical\$3 near2 amplif\$8)	EPO; JPO;	
]			DERWENT;	
			IBM_TDB	
•	1127	430/329 and (resist or photoresist or	USPAT;	2004/07/30
		\$6lithogr\$6) and (strip or stripped or	US-PGPUB;	15:38
		stripping or stripper or remov\$4)	EPO; JPO;	
		,	DERWENT;	
			IBM_TDB	
-	68	(430/329 and (resist or photoresist or	USPAT;	2004/07/30
		\$6lithogr\$6) and (strip or stripped or	US-PGPUB;	15:39
		stripping or stripper or remov\$4)) and	EPO; JPO;	
		(chemical\$3 near2 amplif\$8)	DERWENT;	
		• • • •	IBM_TDB	
	41	((430/329 and (resist or photoresist or	USPAT;	2004/07/30
		\$6lithogr\$6) and (strip or stripped or	US-PGPUB;	15:44
		stripping or stripper or remov\$4)) and	EPO; JPO;	
		(chemical\$3 near2 amplif\$8)) not ((430/329	DERWENT;	
		and (resist or photoresist or \$6lithogr\$6)	IBM_TDB	
		and (strip or stripped or stripping)) and		
		(chemical\$3 near2 amplif\$8))		
	4690	(438/689,694).CCLS.	USPAT;	2004/07/30
			US-PGPUB;	15:44
]		EPO; JPO;	
			DERWENT;	
			IBM_TDB	
<u> </u>	1		<u>-</u>	

	107	(((((((((((((((((((((((((((((((((((((((T	
•	467	((438/689,694).CCLS.) and (resist or	USPAT;	2004/07/30
		photoresist or \$6lithogr\$6) and (strip\$5)	US-PGPUB;	15:53
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
-	14	(((438/689,694).CCLS.) and (resist or	USPAT;	2004/07/30
4		photoresist or \$6lithogr\$6) and (strip\$5))	US-PGPUB;	15:52
	ļ	and (chemical\$3 near2 amplif\$8)	EPO; JPO;	
1			DERWENT;	
			IBM_TDB	
-	3810	(134/1,1.3,26).CCLS.	USPAT;	2004/07/30
		, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	15:53
			EPO; JPO;	13.33
			DERWENT;	
			•	
_	365	(/424/4 4 2 26) COLE) and (maint an	IBM_TDB	
_	303	((134/1,1.3,26).CCLS.) and (resist or	USPAT;	2004/07/30
		photoresist or \$6lithogr\$6) and (strip\$5)	US-PGPUB;	16:38
			EPO; JPO;	
	-		DERWENT;	
			IBM_TDB	
•	0	(((134/1,1.3,26).CCLS.) and (resist or	USPAT;	2004/07/30
		photoresist or \$6lithogr\$6) and (strip\$5))	US-PGPUB;	15:54
		and ((chemical\$3 near amplif\$9) with (Si or	EPO; JPO;	
		silicon or (silicon near (bearining or	DERWENT;	
		containing))))	IBM_TDB	
-	396	(resist or photoresist or photopolymer) with	USPAT;	2004/07/30
		((chemical\$3 near amplif\$9) with (Si or	US-PGPUB;	16:36
		\$6sesquioxane or silane or \$6siloxane or	EPO; JPO;	
		silicon or (silicon near (bearining or	DERWENT;	
		containing))))	IBM_TDB	
_	O	(((134/1,1.3,26).CCLS.) and (resist or	USPAT;	2004/07/30
		photoresist or \$6lithogr\$6) and (strip\$5))	US-PGPUB;	15:56
		and ((resist or photoresist or photopolymer)	EPO; JPO;	15.56
		with ((chemical\$3 near amplif\$9) with (Si or	DERWENT;	
		\$6sesquioxane or silane or \$6siloxane or	1	
		•	IBM_TDB	
		silicon or (silicon near (bearining or]	
_	60	containing)))))		
~	62	(((134/1,1.3,26).CCLS.) and (resist or	USPAT;	2004/07/30
		photoresist or \$6lithogr\$6) and (strip\$5))	US-PGPUB;	16:23
		and (solvent same (THF or PGMEA or DMSO	EPO; JPO;	
		or ketones or esters or lactates))	DERWENT;	
			IBM_TDB	
•	742	(resist or photoresist or photopolymer or	USPAT;	2004/07/30
]	(photo near sensitive)) and ((chemical\$3	US-PGPUB;	17:28
		near amplif\$9) same (Si or \$6sesquioxane	EPO; JPO;	
		or silane or \$6siloxane or silicon or (silicon	DERWENT;	
		near (bearining or containing))))	IBM_TDB	
-	22653	(resist or photoresist or photopolymer or	USPAT;	2004/07/30
		(photo near sensitive)) near6 strip\$5	US-PGPUB;	17:18
		- <i>,,</i> , ,	EPO; JPO;	
			DERWENT;	
			IBM_TDB	;
	اــــــا		I DIVI_I DB	

•	364640	((solvent or solution or strip\$5) same (THF	USPAT;	2004/07/30
		or PGMEA or pgme or DMSO or ketone or esters or lactate))	US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	16:41
-	28	((resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3 near amplif\$9) same (Si or \$6sesquioxane or silane or \$6siloxane or silicon or (silicon near (bearining or containing))))) and ((resist or photoresist or photopolymer or (photo near sensitive)) near6 strip\$5) and (((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 16:42
	22	hardened near photoresist	IBM_TDB	2004/07/30 17:17
•	0	((resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3 near amplif\$9) same (Si or \$6sesquioxane or silane or \$6siloxane or silicon or (silicon near (bearining or containing))))) and (((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate)))	IBM_TDB	2004/07/30 17:17
	445	(resist or photoresist or photopolymer or (photo near sensitive)) near6 (wet near strip\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 17:19
•	3	((resist or photoresist or photopolymer or (photo near sensitive)) and ((chemical\$3 near amplif\$9) same (Si or \$6sesquioxane or silane or \$6siloxane or silicon or (silicon near (bearining or containing))))) and ((resist or photoresist or photopolymer or (photo near sensitive)) near6 (wet near strip\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 17:20
•	40	(((solvent or solution or strip\$5) same (THF or PGMEA or pgme or DMSO or ketone or esters or lactate))) and ((resist or photoresist or photopolymer or (photo near sensitive)) near6 (wet near strip\$5))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/07/30 17:23